



PTO/SB/08B (10-01)
Approved for use through 10/31/2002. OMB 0651-0031
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Complete if Known	
Substitute for form 1449B/PTO		Application Number	09 / 898,521
		Filing Date	July 3, 2001
		First Named Inventor	Charles D. SCHAPER
		Group Art Unit	
		Examiner Name	
Sheet	1 of 1	Attorney Docket Number	STAN MXL 001

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
SPH		Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Imprint Lithography with 25-Nanometer Resolution", Science Vol. 272, April 5, 1996 pp. 85-87, USA.	
SPH		Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Nanoimprint Lithography", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4129-4133, USA.	
SPH		Babak HEIDARI, Ivan MAXIMOV, Eva-Lena SARWE, & Lars MONTELIUS, "Large scale nanolithography using nanoimprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1999 pp. 2962-2964, USA.	
SPH		Jan HAISMA, Martin VERHEIJEN, Kees VAN DEN HEUVEL, & Jan VAN DEN BERG, "Mold-assisted nanolithography: A process for reliable pattern replication", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4124-4128, USA.	
SPH		Thomas WHIDDEN, David FERRY, Michael KOZICKI, Enoch KIM, Amit KUMAR, James WILBUR, & George WHITESIDES, "Pattern transfer to silicon by microcontact and RIE", in Nanotechnology Vol. 7, 1996, pp. 447-451, UK.	
SPH		James WILBUR, Amit KUMAR, Hans BIEBUYCK, Enoch KIM, & George WHITESIDES, "Microcontact printing of self-assembled monolayers: applications in microfabrication", in Nanotechnology Vol. 7, 1996, pp. 452-457, UK.	
SPH		Younan XIA & George WHITESIDES, "Soft lithography", in Annual Reviews of Material Science Vol. 28, 1998, pp. 153-184, USA.	
SPH		Shinichi UEKI, Isao ASHIDA, & Hiroichi KAWAHIRA, "New data processing of dummy pattern generation adaptive for CMP process", in Photomask and X-Ray mask Technology VI, H. Morimoto, ed. Proceedings of the SPIE Vol. 3748, April 1999 pp. 265-272, USA.	
SPH		M. COLBURN, S. JOHNSON, M. STEWART, S. DAMLE, T. TAILEY, B. CHOI, M. WEDLAKE, T. MICHAELSON, S.V. SREENIVASAN, J. EKERDT, & C. Grant WILLSON, "Step and flash imprint lithography: A new approach to high-resolution printing", in Emerging Lithographic Technologies III, Y. Vladimirovsky, ed. Proceedings of the SPIE Vol. 3676, March 1999 pp. 279-389, USA.	
SPH		P. RUCHHOEFT, M. COLBURN, B. CHOI, H. NOUNU, S. JOHNSON, T. BAILEY, S. DAMLE, M. STEWART, J. EKERDT, S.V. SREENIVASAN, J.C. WOLFE, & C. Grant WILLSON, "Patterning curved surfaces: Template generation by ion beam proximity lithography and relief transfer by step and flash imprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1996 pp. 2965-2969, USA.	

Examiner Signature	Mohamedulla	Date Considered	8/9/04
--------------------	-------------	-----------------	--------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

RECEIVED
JUN 18 2002
TC 1700